

Engineering Conferences International ECI Digital Archives

Nanomechanical Testing in Materials Research and
Development V

Proceedings

Fall 10-6-2015

Size effects and deformation mechanisms in diamond and silicon

Jeffrey Wheeler
ETH Zurich

R. Raghavan
Max Plank Institute

J. Rabier
CNRS

J. Wehrs
Empa, Swiss Federal Laboratories for Materials Science and Technology

J. Michler
Empa, Swiss Federal Laboratories for Materials Science and Technology

Follow this and additional works at: http://dc.engconfintl.org/nanomechtest_v

 Part of the [Materials Science and Engineering Commons](#)

Recommended Citation

- [1] B. Kedjar, L. Thilly, J.L. Demenet, J. Rabier, *Acta Materialia*, 58 (2010) 1426-1440. [2] T. Suzuki, T. Yasutomi, T. Tokuoka, I. Yonenaga, *Physica status solidi (a)*, 171 (1999) 47-52. [3] J. Michler, K. Wasmer, S. Meier, F. Ostlund, K. Leifer, *Applied Physics Letters*, 90 (2007) 043123-043123. [4] L. Thilly, R. Ghisleni, C. Swistak, J. Michler, *Philos. Mag.*, (2012) 1-11. [5] S. Korte, W.J. Clegg, *Scripta Materialia*, 60 (2009) 807-810. [6] J.M. Wheeler, C. Niederberger, C. Tessarek, S. Christiansen, J. Michler, *International Journal of Plasticity*, 40 (2013) 140-151

SIZE EFFECTS AND DEFORMATION MECHANISMS IN DIAMOND AND SILICON

J.M. Wheeler, Laboratory for Nanometallurgy, ETH Zurich, Vladimir-Prelog-Weg 5, Zurich 8005, Switzerland
Jeff.Wheeler@mat.ethz.ch

R. Raghavan, Structure and Nano-/Micromechanics of Materials, Max-Planck-Institute für Eisenforschung GmbH, Max-Planck-Strasse 1, 40237 Düsseldorf, Germany

J. Rabier, Institut P', CNRS-University of Poitiers-ENSMA, SP2MI, 86962 Futuroscope, France

J. Wehrs, J. Michler,

Empa, Swiss Federal Laboratories for Materials Science and Technology, Laboratory for Mechanics of Materials and Nanostructures, Feuerwerkerstrasse 39, Thun CH-3602, Switzerland

Key words: microcompression, rate sensitivity, size effects, semiconductors

At ambient temperature and pressure, most of the semiconductor materials are brittle. Traditionally, use of confining pressure via indentation or a hydrostatic confining medium [1, 2] has been required to study the plasticity of such brittle materials. In the case of group IV semiconductors (Diamond, Silicon, and Germanium) the situation is further complicated by pressure-induced phase transformations occurring underneath the indentations. However, previous work has demonstrated that sample miniaturization can also prevent the onset of cracking and allow plastic deformation [3]. Recent advances in *in situ* instrumentation have enabled micro-compression techniques to extract temperature- and time-dependent deformation parameters [5, 6]. Thus, micro-pillar compression is a promising technique for investigating the plasticity of these semiconductors in their brittle regimes.

Previous work has noted a brittle-ductile transition in Silicon which is dependent on orientation, size, and temperature. This has been tied to transitions between partial and perfect dislocations in III-V semiconductors, but the extreme brittle character of silicon has prevented characterization of plastic flow in the low temperature regimes. In this work, [123]-oriented crystals are utilized to prevent the onset of cracking and allow plastic deformation. Micro-compression is shown to be capable of achieving incredibly high stresses (>100 GPa), and this is applied to investigate the behavior of the hardest natural material - diamond - and its nearest analog – silicon.

References

- [1] B. Kedjar, L. Thilly, J.L. Demenet, J. Rabier, *Acta Materialia*, 58 (2010) 1426-1440.
- [2] T. Suzuki, T. Yasutomi, T. Tokuoka, I. Yonenaga, *Physica status solidi (a)*, 171 (1999) 47-52.
- [3] J. Michler, K. Wasmer, S. Meier, F. Ostlund, K. Leifer, *Applied Physics Letters*, 90 (2007) 043123-043123.
- [4] L. Thilly, R. Ghisleni, C. Swistak, J. Michler, *Philos. Mag.*, (2012) 1-11.
- [5] S. Korte, W.J. Clegg, *Scripta Materialia*, 60 (2009) 807-810.
- [6] J.M. Wheeler, C. Niederberger, C. Tessarek, S. Christiansen, J. Michler, *International Journal of Plasticity*, 40 (2013) 140-151.